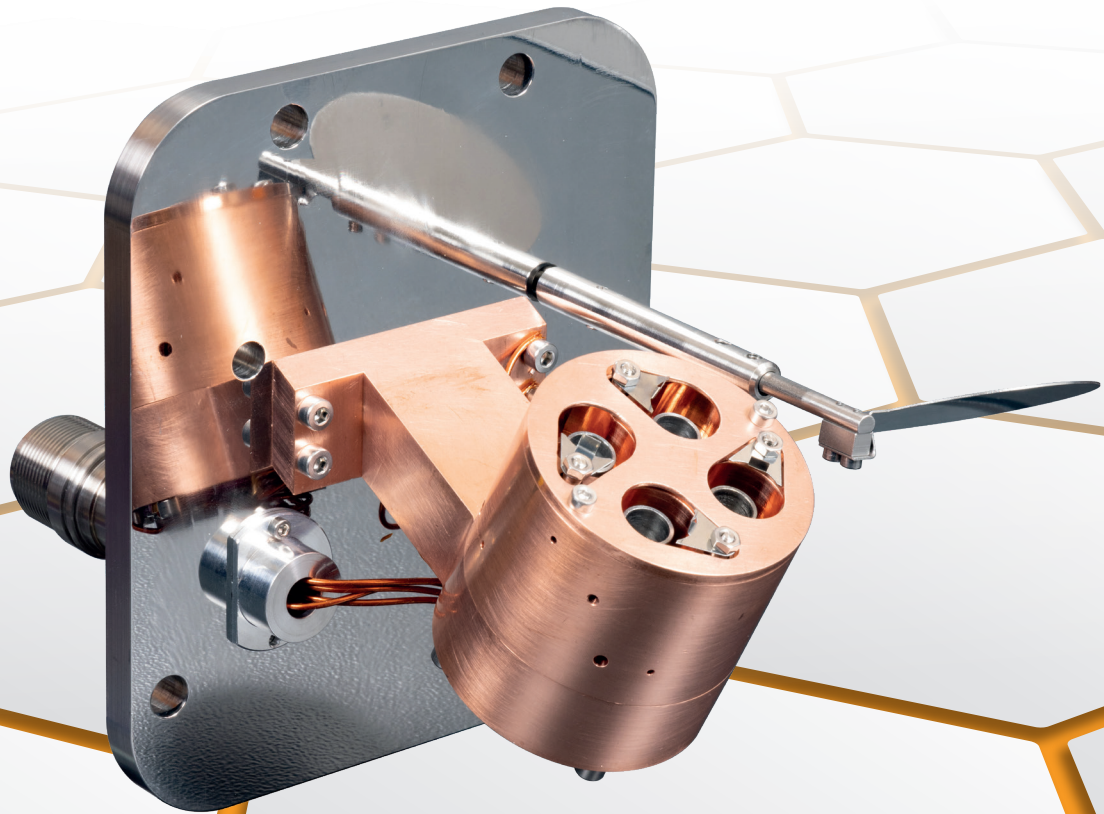




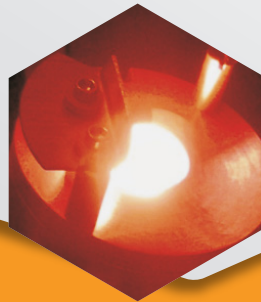
KORVUS TECHNOLOGY

TAU

ELECTRON BEAM
EVAPORATION
SOURCE



Co-evaporation
of up to 4 materials



Metallisation
Lift-off process
Refractory materials

WWW.KORVUSTECH.COM

Unit 1 Kings Grove Industrial Estate | Maidenhead | Berkshire | SL6 4DP | UK
T: +44 1628 201329 E: info@korvustech.com

TAU

Electron-beam evaporation allows direct heating of target materials and is capable of evaporating challenging materials such as Tungsten.

Alternative thermal evaporation techniques employ radiative heating, limiting the evaporation temperature of the target to substantially below the temperature of the heating element. In E-beam evaporation, a high-energy electron beam is directed towards the target material, thereby heating it to evaporation temperature.

The TAU evaporators are 'mini' sources, which operate with the target material at high voltage and the emission filament at low voltage, eliminating the need for beam-bending magnets.

The sources accept either rods of conducting target materials or crucibles which can hold metallics. The TAU is recommended for metals only for film thicknesses from sub-mono-layer to 200nm.

The TAU sources use an enclosed, cooled head, ensuring that the thermal load on the chamber is reduced to a minimum. This makes the sources useful for evaporation onto sensitive substrates, allowing efficient use of expensive materials such as gold when evaporated from a collimating crucible.

	TAU-S	TAU-4
Pockets	1	4
Maximum Power Per Pocket	250W	250W
Materials	Rods (max 4mm dia), Crucibles	Rods (max 4mm dia), Crucibles
Co-evaporation	No	Yes
Cooling	Water (min 0.5l/min)	Water (min 0.5l/min)

